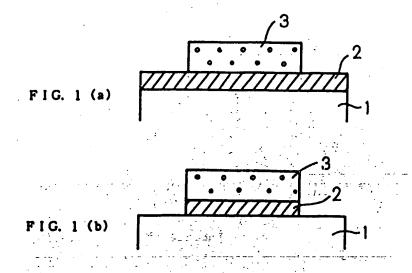
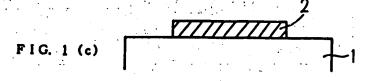
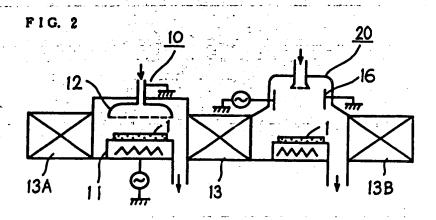
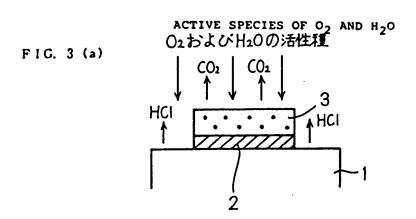
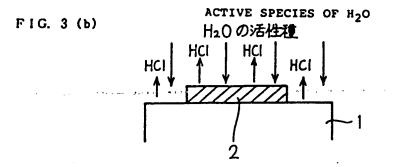
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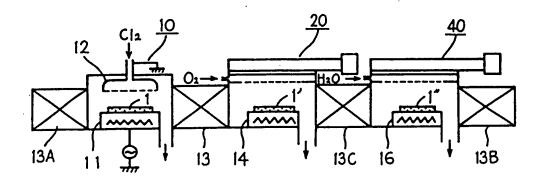


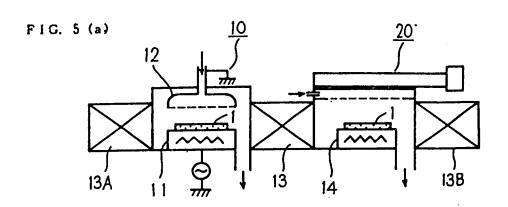






F1G. 4





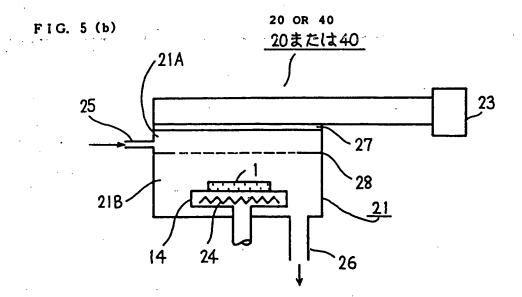


FIG. 6

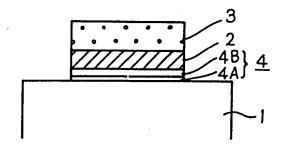
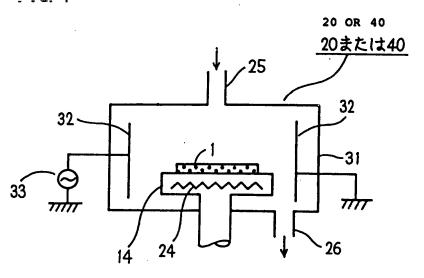


FIG. 7



F1G. 8

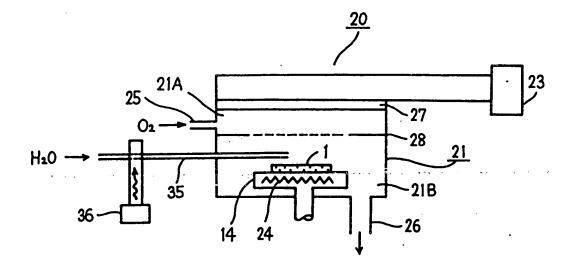


FIG. 9

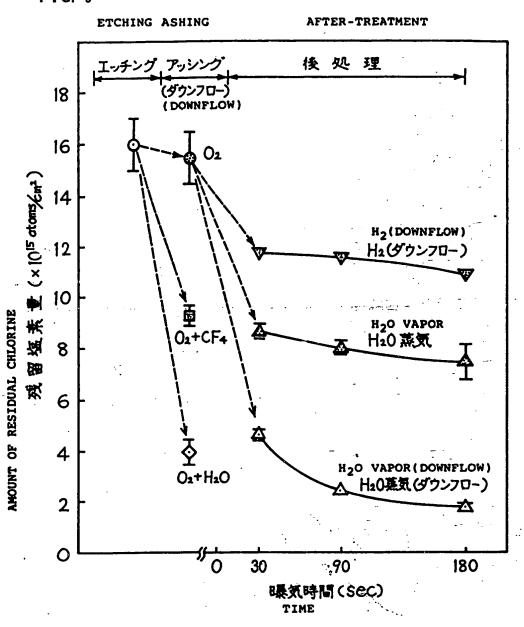


TABLE OF REFERENCE NUMERALS 参照符号・事項の一覧表

ľ.	1 .	•	1	•	•	•	•	基板.	SUBSTRATE
2 •		ア	ル	E	_	ウ	ム	膜.	ALUMINUM FILM
3 .		マ	ス	2	•				MASK
4 •		/<	ij	ヤ	¥	夕	ル	•	BARRIER METAL
10 •		RI	E	装					RIE APPARATUS
11,	14 •	•	•	ス	テ	-	シ	•	STAGE
12,	16.	32	.	•	•	Æ	極	•	ELECTRODE
13.	13A	. 1	3 B	},	13	C	•		・ドロック室, LOAD LOCK CHAMBER
20 •		7	ッ	シ	ン	7	蒆	懂.	ASHING APPARATUS
21.	31 •	•	•	チ	ヤ	ン	ノく	•	CHAMBER
21 A		•	プ	ラ	ズ	マ	発	生室,	PLASMA GENERATING CHAMBER
21 B	• •	•	7	ッ	シ	ン	グ	室.	ASHING CHAMBER
23,	36 •	•	•	マ	1	2		波発生源	. MICROWAVE GENERATION SOURCE
24 •		٤	_	夕	•				HEATER
25,	·35 ·	•	•	ガ	ス	導	入	管.	GAS INTRODUCTION PIPE
26 •	.• •	排	戾	管					EXHAUST PIPE
28 •		シ	+	ヮ	_	^	ッ	۴.	SHOWER HEAD
33 •		高	周	波	Æ	源	•	÷	HIGH FREQUENCY POWER SUPPLY
40 •		後	処	瑾	袋				AFTER-TREATMENT APPARATUS